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PATENT & TRADEMARK OFFICE

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Entley, William R.; Langan, John G.; Hall, Randy
Assignee: Novellus Systems, Inc.
Title: In Situ Plasma Process To Remove Fluorine Residues From The Interior Surfaces Of A CVD Reactor
Serial No.: 10/003,908 Filing Date: November 1, 2001
Examiner: Unassigned Group Art Unit: Unassigned
Docket No.: M-11021 US

San Jose, California
March 8, 2002

COMMISSIONER FOR PATENTS
Washington, D.C. 20231

INFORMATION DISCLOSURE STATEMENT
UNDER 37 CFR § 1.97(b)

Dear Sir:

Pursuant to 37 C.F.R. § 1.56, § 1.97 and § 1.98, the documents listed on the accompanying form PTO-1449 are called to the attention of the Examiner for the above patent application. Copies of these documents are enclosed.

Citation of these documents shall not be construed as:

1. an admission that the documents are necessarily prior art with respect to the instant invention;
2. a representation that a search has been made; or
3. an admission that the information cited herein is, or is considered to be, material to patentability as defined in § 1.56(b).

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231, on March 8, 2002.

Attorney for Applicant(s)

Date of Signature

Respectfully submitted,

Edward C. Kwok
Attorney for Applicants
Reg. No. 33,938

LAW OFFICES OF
SKJERNEN MORRILL
MILNERSON LLP

25 METRO DRIVE
SUITE 200
SAN JOSE, CA 95110
(408) 453-9200
FAX (408) 453-7979